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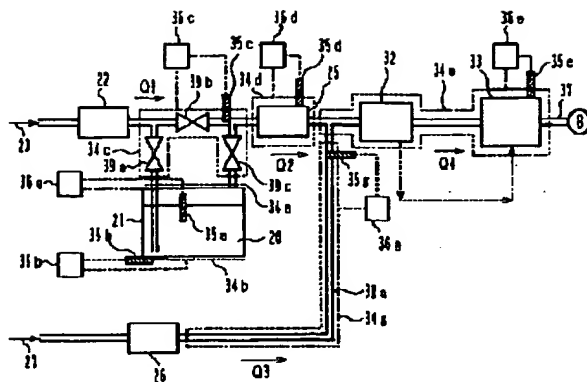
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TITLE : CHEMICAL VAPOR GROWTH DEVICE



ABSTRACT : **PROBLEM TO BE SOLVED:** To enable the precise flow rate control of a vaporized gas and to improve the reliability in film formation in a chemical growth device in which a vaporized gas produced by vaporizing a liq. material by bubbling is diluted by the introduction of a carrier gas and is fed to a reaction chamber to form a film.

SOLUTION: A liq. raw material 20, a piping system 38a introducing a carrier gas 27 and a piping system 37 feeding a gaseous starting material to a reaction chamber are provided with heaters 34, and each heater 34 provided on the piping systems 37 and 38a has a mechanism of directly monitoring the gas temp. in the piping to control it to the prescribed one, prevents the liquefaction of the vaporized gas and feeds a stable flow rate.

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